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### **Education:**

Ph.D., Applied Physics, California Institute of Technology 1982 M.S., Applied Physics, California Institute of Technology 1980 B.Ap.Sc., Engineering Physics, University of British Columbia 1978

### **Honors & Awards:**

American Physical Society Outstanding Referee, 2009
Alexander von Humboldt Foundation Research Award, 2000
Fellow of the American Physical Society, 1998
Fellow of the American Vacuum Society, 1994
Peter Mark Memorial Award of the American Vacuum Society, 1989
IBM Outstanding Innovation Award, 1987
Natural Sciences and Eng. Research Council of Canada Scholarship, 1978–82
Academic Honors, University of British Columbia, 1978
Engineering Physics Scholarship, U.B.C., 1977

## **Experience**

6/01–12/01, Humboldt Visiting Professor, Technical University, Berlin 9/95–present, Professor, Dept. Physics, Carnegie Mellon University 7/82–8/95, IBM Research, Yorktown Heights, Research Staff Member 9/78–6/82, California Institute of Technology, Graduate Student:

# **Publications & Presentations:**

More than 230 publications in refereed journals, 7 book chapters, over 70 seminars at academic, government or industrial institutions, and over 100 conference presentations (the majority of which were invited). The publications have been cited more than 10,000 times in scientific journals, and they carry an h-index of 55 (Web of Science).

#### **Patents:**

- 1) Narrow Line Width Pattern Fabrication, G. Binnig, R. M. Feenstra, R. T. Hodgson, H. Rohrer, and J. M. Woodall, U.S. patent number 4550257, Oct. 29, 1985.
- 2) In-situ Endpoint Detection Method and Apparatus for Chemical-Mechanical Polishing,
- R. M. Feenstra, W. L. Guthrie and N. E. Lustig, U.S. patent number 5337015, 2)